

Electronic Acknowledgement Receipt

EFS ID:	1384855
Application Number:	10791763
International Application Number:	
Confirmation Number:	4420
Title of Invention:	Set of at least two masks for the projection of structure patterns and method for producing the masks
First Named Inventor/Applicant Name:	Wolfgang Dettmann
Customer Number:	27896
Filer:	Patrick J. Finnan/Paula Verkuilen
Filer Authorized By:	Patrick J. Finnan
Attorney Docket Number:	0928.0036C
Receipt Date:	19-DEC-2006
Filing Date:	04-MAR-2004
Time Stamp:	18:03:51
Application Type:	Utility

Payment information:

Submitted with Payment	no
------------------------	----

File Listing:

Document Number	Document Description	File Name	File Size(Bytes)	Multi Part /.zip	Pages (if appl.)
1		SuppRestrictionResponse.pdf	112061	yes	6

	Multipart Description/PDF files in .zip description		
	Document Description	Start	End
	Miscellaneous Incoming Letter	1	1
	Supplemental Response or Supplemental Amendment	2	6

Warnings:

Information:

Total Files Size (in bytes):

112061

This Acknowledgement Receipt evidences receipt on the noted date by the USPTO of the indicated documents, characterized by the applicant, and including page counts, where applicable. It serves as evidence of receipt similar to a Post Card, as described in MPEP 503.

New Applications Under 35 U.S.C. 111

If a new application is being filed and the application includes the necessary components for a filing date (see 37 CFR 1.53(b)-(d) and MPEP 506), a Filing Receipt (37 CFR 1.54) will be issued in due course and the date shown on this Acknowledgement Receipt will establish the filing date of the application.

National Stage of an International Application under 35 U.S.C. 371

If a timely submission to enter the national stage of an international application is compliant with the conditions of 35 U.S.C. 371 and other applicable requirements a Form PCT/DO/EO/903 indicating acceptance of the application as a national stage submission under 35 U.S.C. 371 will be issued in addition to the Filing Receipt, in due course.